

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 04-333573

(43)Date of publication of application : 20.11.1992

(51)Int.Cl.

C23C 16/50

(21)Application number : 03-132182

(71)Applicant : CANON INC

(22)Date of filing : 09.05.1991

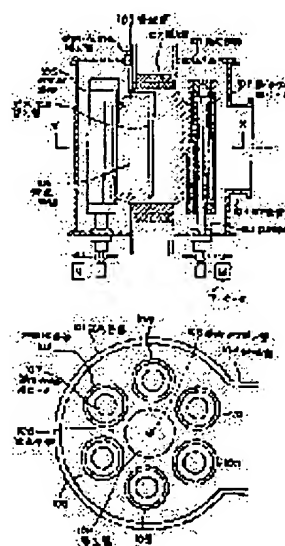
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(54) MICROWAVE PLASMA CVD APPARATUS

(57)Abstract:

PURPOSE: To offer an apparatus for forming a deposited film capable of stably forming a functional deposited film having good properties at low cost in high yield at high speed by a microwave plasma CVD method.

CONSTITUTION: As for a microwave introducing window 102, alumina is used as a base metal, to which partially stabilized zirconia is added in the range of 1 to 90% and is uniformly dispersed, and baking is executed into an alumina-zirconia base composite. In this way, its durability to severe use by the repetition of the formation of a film on a microwave introducing window by a microwave plasma CVD method and the removal of the deposited film as posttreatment after the film forming can be improved.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of

rejection]

[Date of requesting appeal against examiner's
decision of rejection]

[Date of extinction of right]

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